

This listing of claims will replace all prior versions, and listings, of claims in the application:

**THE STATUS OF THE CLAIMS**

1. (Cancelled)
2. (Original) A chemical mechanical polishing (CMP) method of planarizing a pattern of a wafer by rotating the wafer that is fixed to a carrier head, on a polishing pad by pressing the wafer against the polishing pad and injecting slurry onto the polishing pad, the method comprising:
  - performing a first planarization process by injecting the slurry onto the polishing pad and rotating the wafer as the wafer contacts the polishing pad; and
  - performing a second planarization process during which the wafer is spaced apart from the polishing pad at a given spacing, wherein air is injected into the polishing pad to produce bubbles in the slurry on the polishing pad while the wafer is rotated.
3. (Original) A chemical mechanical polishing method as defined by claim 2, wherein in the second planarization process, a concentration of the slurry on the polishing pad is higher than that of the slurry used in the first planarization process.
4. (Original) A chemical mechanical polishing method as defined by claim 2, wherein the spacing between the wafer and the polishing pad is 5 to 10 mm.
5. (Original) A chemical mechanical polishing method as defined by claim 3, wherein the concentration of the slurry used in the second planarization process is 2 to 3 times higher than that of the slurry used in the first planarization process.
6. (Original) A chemical mechanical polishing method as defined by claim 2, wherein a pattern thickness of the wafer polished through the first planarization process is 70 to 80% of a total planarization thickness.